

Measurement of: Fabrication of micron sized patterns with photoresist

Equipment: UV-Photo lithography facility

Property Measured: Fabrication of micron sized patterns with photoresist.

Photograph (small size)



Basic Principle: This is an integral part of Argon Ion Milling and Focused Ion Beam (FIB) milling facilities for device fabrication. It includes programmable spin coater with vacuum chuck, baking oven and UV exposure unit. Together with Argon Ion Milling this system has been regularly in use for making micron size pattern for MTJ studies.

Capabilities: Down to 5 micron feature size can be realized

Sample Requirement: Thin film samples